Rigaku

Monitoring Surface Contamination with TXRF

Total Reflection X-ray Fluorescence Spectrometer

Non-destructive and Non-contracting Surface Contamination Analysis

TXRF 3760

- Analysis Range:Na､Mg, Al~U
- High Throughput & High Sensitivity
- Liquid Nitrogen Free
- For 50 mm to 200 mm Wafers

High performance

TXRF 3800e

- Liquid Nitrogen Free
- Reduced Power Consumption
- For 50 mm to 200 mm Wafers

Low COO

Lower Limit of Detection (LLD) Examples for Specific Elements

Atoms/cm²	Na	Al	Fe	Ni	Cu
TXRF 3760	2.5×10^{11}	2.5×10^{11}	1.0×10^{9}	1.0×10^{9}	1.5×10^{9}
TXRF 3800e	-	-	2.1×10^{9}	1.8×10^{9}	1.9×10^{9}

Applications: Si, SiC, GaN, Ga_2O_3, Diamond, ･･･